EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L4	2	"6872509"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 13:15
L5	130	($4lithograph$4 or exposure) and ((transfer$4 or exposi$4 or project$4) same (first adj3 (mask or reticle)) same (second adj3 (mask or reticle)) same (simultaneous$4 or concurren$4 or ("same time")) same (substrate or wafer))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 15:01
L6	21	5 and (projection adj3 (lens or optical or system or device or apparatus))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 13:19
L7	30414	(second adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning)) near5 (position$4 or plac$4 or locat$4) near4 between (first adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 15:05
L8	6530	(second adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning)) near5 (position$4 or plac$4 or locat$4) near4 between (first adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning)) near5 (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 15:06
L9	10	(second adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning)) near5 (position$4 or plac$4 or locat$4) near4 between near5 (first adj2 (mask or reticle or (spatial adj2 light adj2 modulat$4) or SLM or patterning)) near5 (wafer or substrate)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 15:06
L10	2	"7081945"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 15:12

L11	33	"4758863"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 15:12
S1	20	("20020025019"|"20020177076"|"5194344"|"5194346"|"5308741"|"5384219"|"5851704"|"5906910"|"5908718"|"6498105").PN.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 15:10
S2	31099	($4lithograph$4 or exposure) and (second adj3 (mask or pattern$4 or reticle))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 13:15
S3	124	S2 and (second adj2 (mask or reticle)) near7 (locat$4 or position$4 or plac$4 or dispos$4) near4 (between) near5 (first adj3 (mask or reticle))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 10:52
S4	49	S3 and (substrate or wafer or photosensitive or photoreactive) and (projection adj2 (optical or lens or system or device))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2007/07/25 11:52
S5	15	"5995200"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 12:05
S6	33	"4758863"	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 12:08
S7	2	"4758863".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 12:09
S8	2	"6872509".pn.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	OFF	2007/07/25 13:14